

10/ 711, 379

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("5753566").PN.	USPAT	OR	OFF	2005/04/26 12:07
L2	1	("6024828").PN.	USPAT	OR	OFF	2005/04/26 12:07
L3	1	("6482716").PN.	USPAT	OR	OFF	2005/04/26 12:08
L4	1	("6630397").PN.	USPAT	OR	OFF	2005/04/26 12:08
L5	1	4 and (chilled or water or helium or surface or openings or plurality or spin or on or material or temperature or "50" or glass or dielectric or etch or etching or plasma or expose or fluid or gas or liquid or region or sparse or dense or trench or photo or resist or coating or cooled or cooling or wafer)	USPAT	OR	ON	2005/04/26 12:15
L6	1	3 and (chilled or water or helium or surface or openings or plurality or spin or on or material or temperature or "50" or glass or dielectric or etch or etching or plasma or expose or fluid or gas or liquid or region or sparse or dense or trench or photo or resist or coating or cooled or cooling or wafer)	USPAT	OR	ON	2005/04/26 12:18
L7	1	2 and (chilled or water or helium or surface or openings or plurality or spin or on or material or temperature or "50" or glass or dielectric or etch or etching or plasma or expose or fluid or gas or liquid or region or sparse or dense or trench or photo or resist or coating or cooled or cooling or wafer)	USPAT	OR	ON	2005/04/26 12:19
L8	1	1 and (chilled or water or helium or surface or openings or plurality or spin or on or material or temperature or "50" or glass or dielectric or etch or etching or plasma or expose or fluid or gas or liquid or region or sparse or dense or trench or photo or resist or coating or cooled or cooling or wafer)	USPAT	OR	ON	2005/04/26 12:19
L9	431	438/9	USPAT	OR	ON	2005/04/26 12:45
L10	2012	438/424	USPAT	OR	ON	2005/04/26 12:45
L11	759	438/427	USPAT	OR	ON	2005/04/26 12:45
L12	644	438/636	USPAT	OR	ON	2005/04/26 12:45

L13	3113	438/637	USPAT	OR	ON	2005/04/26 12:45
L14	1469	438/700	USPAT	OR	ON	2005/04/26 12:46
L15	353	438/737	USPAT	OR	ON	2005/04/26 12:46
L16	980	438/738	USPAT	OR	ON	2005/04/26 12:46
L17	517	438/704	USPAT	OR	ON	2005/04/26 12:46
L18	395	438/715	USPAT	OR	ON	2005/04/26 12:46
S11 9	0	(spin adj on adj material) and (plasma adj etching adj process)	USPAT	OR	ON	2005/04/26 11:07
S12 0	0	(spin adj on adj material)	USPAT	OR	ON	2005/04/26 11:07
S12 1	51	spin and cool and substrate and(plasma adj etching adj process)	USPAT	OR	ON	2005/04/26 11:08
S12 2	33	spin and cool and substrate and(plasma adj etching adj process) and surface and opening	USPAT	OR	ON	2005/04/26 11:09
S12 3	8	spin and cool and substrate and(plasma adj etching adj process) and surface and opening and helium and water	USPAT	OR	ON	2005/04/26 11:10
S12 4	3	spin and cool and substrate and(plasma adj etching adj process) and surface and opening and helium and (chilled adj water)	USPAT	OR	ON	2005/04/26 12:45
S12 5	8	S123 and (chilled or water or helium or surface or openings or plurality or spin or on or material or temperature or "50" or glass or dielectric or etch or etching or plasma or expose or fluid or gas or liquid or region or sparse or dense or trench or photo or esist)	USPAT	OR	ON	2005/04/26 12:08